

Form PTO-1449

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

(Use several sheets if necessary)

ATTY. DOCKET NO. 0171-1098PUS1	APPLICATION NO. NEW
APPLICANT Takeru WATANABE, et al.	
FILING DATE May 20, 2004	GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	KIND	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JES	US 5,691,100	A	1997-11-25	Kudo, et al.			
	US 5,525,453	A	1996-06-11	Przybilla, et al.			
	US 5,843,319	A	1998-12-01	Przybilla, et al.			
	US 5,612,169	A	1997-03-18	Eichhorn, et al.			
	US 5,529,886	A	1996-06-25	Eichhorn, et al.			
	US 5,442,087	A	1995-08-15	Eichhorn, et al.			
	US 6,703,181	B1	2004-03-09	Hayashi, et al.			
	US 5,658,706	A	1997-08-19	Niki, et al.			
	US 5,744,281	A	1998-04-28	Niki, et al.			
	US 6,004,724	A	1999-12-21	Yamato, et al.			

FOREIGN PATENT DOCUMENTS

Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
							YES	NO
JPS	JP 2-27660	B2	1990-06-19	JAPAN			ABS	
	JP 63-27829	A	1988-02-05	JAPAN			ABS	
	JP 5-232706	A	1993-09-10	JAPAN			ABS	
	JP 5-249683	A	1993-09-28	JAPAN			ABS	
	JP 5-158239	A	1993-06-25	JAPAN			ABS	
	JP 5-249662	A	1993-09-28	JAPAN			ABS	
	JP 5-257282	A	1993-10-08	JAPAN			ABS	
	JP 5-289322	A	1993-11-05	JAPAN			ABS	
	JP 5-289340	A	1993-11-05	JAPAN			ABS	

OTHER DOCUMENTS (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)

- JES HINSBERG et al., "Fundamental studies of airborne chemical contamination of chemically amplified resists", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 535-546.
- () KUMADA et al., "Study on over-top coating of positive chemical amplification resists for KrF excimer laser lithography", Journal of Photopolymer Science and Technology, Vol. 6, No. 4, 1993, 571-574.
- () HATAKEYAMA et al., "Investigation of discrimination enhancement with new modeling for poly-hydroxystyrene positive resists", Journal of Photopolymer Science and Technology, Vol. 13, No. 4, 2000, 519-524.

EXAMINER <i>JCH</i>	DATE CONSIDERED <i>9/20/05</i>
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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EXAMINER INITIAL	DOCUMENT NUMBER	KIND	DATE	NAME	CLASS SUB CLASS FILING DATE IF APPROPRIATE		
<i>JL</i>	US 6,261,738	B1	2001-07-17	Asakura, et al.			
<i>JL</i>	US						
<i>JL</i>	US						
FOREIGN PATENT DOCUMENTS							
Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS SUB CLASS	TRANSLATION	
					YES	NO	
JP	6-194834	A	1994-07-15	JAPAN			ABS
JP	6-242605	A	1994-09-02	JAPAN			ABS
JP	6-242606	A	1994-09-02	JAPAN			ABS
JP	6-263716	A	1994-09-20	JAPAN			ABS
JP	6-263717	A	1994-09-20	JAPAN			ABS
JP	6-266100	A	1994-09-22	JAPAN			ABS
JP	6-266111	A	1994-09-22	JAPAN			ABS
JP	7-128859	A	1995-05-19	JAPAN			ABS
JP	7-92678	A	1995-04-07	JAPAN			ABS
JP	7-92680	A	1995-04-07	JAPAN			ABS
JP	7-92681	A	1995-04-07	JAPAN			ABS
JP	7-120929	A	1995-05-12	JAPAN			ABS
JP	7-134419	A	1995-05-23	JAPAN			ABS
JP	2000-314956	A	2000-11-14	JAPAN			ABS
JP	9-95479	A	1997-04-08	JAPAN			ABS
JP	9-230588	A	1997-09-05	JAPAN			ABS
JP	9-208554	A	1997-08-12	JAPAN			ABS
OTHER DOCUMENTS (Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)							
EXAMINER					DATE CONSIDERED	<i>9/10/04</i>	
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